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[2345/17A]

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s) : Rainer LOESCH, et al.
Serial No. : 09/750,837
Filed : December 28, 2000
Title : CALIBRATED SCALE IN THE NANOMETER RANGE FOR
TECHNICAL DEVICES USED FOR THE HIGH-
RESOLUTION OR ULTRAHIGH-RESOLUTION IMAGING
OF STRUCTURES
Art Unit : 1774
Examiner : Lawrence Ferguson

Commissioner for Patents
Washington, D.C. 20231

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Date: 7/17/02

Signature

Linda M. Shudy (Reg. No. 47,084)

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AMENDMENT

SIR:

In response to the Office Action having mailing date of January 17, 2002, please
reconsider the above-identified application based on the following.

IN THE CLAIMS:

Please amend without prejudice claim 1 as follows:

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1. (Amended) A scale for technical devices which are used for high-resolution or ultrahigh-
resolution imaging of structures, the scale comprising:

a plurality of one of crystalline and amorphous first material layers having a
first thickness; and

a plurality of one of crystalline and amorphous second material layers which
are distinguishable from the first material layers when imaged using high-resolution or
ultrahigh-resolution imaging methods, the second material layers having a second
thickness and the first material layers alternating with the second material layers;

at least one of the first and second material layers having a thickness of less
than twenty-five nanometers.

AX
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